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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/892,419	06/26/2001	Chong-Yao Chen	JC-7485-DIV	2790	
7590 12/09/2004			EXAMINER		
CHARLES C.H. WU & ASSOCIATES			NGO, NGAN V		
Suite 710 7700 IRVINE CENTER DRIVE			ART UNIT	PAPER NUMBER	
Irvine, CA 92618-3043			2814	-	

DATE MAILED: 12/09/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		A 11 41 11	1 1 1/1				
		Application No.	Applicant(s)	- ,,-			
Office Action Summary		09/892,419	CHEN ET AL.				
	Office Action Summary	Examiner	Art Unit				
		Ngan Ngo	2814	·			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
THE - Exte after - If the - If NC - Failt Any	ORTENED STATUTORY PERIOD FOR REPL' MAILING DATE OF THIS COMMUNICATION. nsions of time may be available under the provisions of 37 CFR 1.1: SIX (6) MONTHS from the mailing date of this communication. e period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period of the property of the property within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tin y within the statutory minimum of thirty (30) day vill apply and will expire SIX (6) MONTHS from , cause the application to become ABANDONE	nely filed  /s will be considered timely  the mailing date of this co  ED (35 U.S.C. § 133).	r. Immunication.			
Status			,				
1)	Responsive to communication(s) filed on		•				
2a)□		action is non-final.					
3)□	Since this application is in condition for allowar	nce except for formal matters, pro	osecution as to the	merits is			
•	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims							
4)  🔀	Claim(s) <u>1-8</u> is/are pending in the application.						
- ا	4a) Of the above claim(s) is/are withdraw	wn from consideration					
5)□	Claim(s) is/are allowed.						
·	6)⊠ Claim(s) <u>1-8</u> is/are rejected.						
7)	Claim(s) is/are objected to.						
8)□	Claim(s) are subject to restriction and/o	r election requirement.					
Applicat	ion Papers	. ·					
_		ır					
9)∐ The specification is objected to by the Examiner.  10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).							
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority (	under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).							
	☐ All b)☐ Some * c)☐ None of:		, (a) 5. (.).				
	1. Certified copies of the priority document	s have been received.					
•	2. Certified copies of the priority document		ion No				
	3. Copies of the certified copies of the prior	• •		Stage			
	application from the International Bureau	•					
* (	See the attached detailed Office action for a list	• • • • • • • • • • • • • • • • • • • •	ed.				
Attachmen	it(s)						
1) Notice of References Cited (PTO-892)  4) Interview Summary (PTO-413)							
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date							
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)  Paper No(s)/Mail Date  5) Notice of Informal Patent Application (PTO-152)  6) Other:							

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The specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-5, 7, and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Applicants' prior art figure 1 in view of Kuriyama et al.

Applicants' prior art figure 1 discloses a CMOS image sensor comprising a substrate (100), a photodiode sensory region (110), a transistor region (120) having a gate oxide (104), a gate conductive layer (106), a spacer and source/drain region (108), and a self-aligned block (116). However, Applicants' prior art failed to disclose the protective layer covering the self-aligned block. Kuriyama discloses a CMOS image sensor comprising a silicon nitride protective layer (15a) formed on an oxide layer (11) which can be considered as the oxide block to reduce reflection of the light. Therefore, it would have been obvious to one of ordinary skill in the art to form an silicon nitride layer on the self-aligned block of Applicants' prior art figure 1 in order to protect the surface of the block and to reduce reflection of the light as taught by Kuriyama.

In re claim 2, the silicon nitride taught by Kuriyama inherently prevents erosion from plasma etching.

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In re claim 5, the self-aligned sensory region (112) and the source/drain region (108) are implanted as the same time and therefore they have the same dopant type.

In re claims 7 and 8, it is well-known in the art that the photodiode and the substrate have opposite dopant type.

Claims 6 rejected under 35 U.S.C. 103(a) as being unpatentable over Applicants' prior art figure 1 in view of Kuriyama et al as applied to claims 1-5, 7, and 8 above, and further in view of Hsieh et al.

Hsieh disclose a CMOS image sensor in which the gate, source, and drain of the transistor is covered with silicide in order to reduce the resistance of the contact region. Therefore, it would have been obvious to one of ordinary skill in the art to form the silicide layer in Applicants' prior art device in order to reduce the contact resistance as taught by Hsieh.

The other references are cited to show other structures pertinent to Applicants' disclosure.

Paper copies of cited U.S. patents and U.S. patent application publications will cease to be mailed to applicants with Office actions as of June 2004. Paper copies of foreign patents and non-patent literature will continue to be included with office actions. These cited U.S. patents and patent application publications are available for download via the Office's PAIR. As an alternate source, all U.S. patents and patent application publications are available on the USPTO web site (<a href="www.uspto.gov">www.uspto.gov</a>), from the Office of Public Records and from commercial sources. Applicants are referred to the Electronic Business Center (EBC) at <a href="http://www.uspto.gov/ebc/index.html">http://www.uspto.gov/ebc/index.html</a> or 1-866-217-9197 for information on this policy. Requests to restart a period for response due to a missing U.S. patent or patent application publications will not be granted.

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Any inquiry concerning this communication should be directed to Examiner Ngan Ngo at telephone number (571) 272-1711. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Ngan Van Ngo Primary Examiner

Ngan Ngo

December 7, 2004